WHAT IS CLAIMED IS:

1. A cleaning apparatus for cleaning a workpiece, comprising:

a holding unit for holding an outer circumferential portion of the workpiece thereon;

a rotating mechanism for rotating the holding unit; and

a cleaning unit for cleaning a reverse side of the workpiece,

wherein the cleaning unit includes a cleaning member for contacting the reverse side of the workpiece and a drive mechanism for moving the cleaning member toward and away from the reverse side of the workpiece, and

wherein the workpiece includes a wafer, a sheet fixed to the wafer, and an annular frame supporting the wafer through the sheet,

the holding unit holds the frame thereon, and

the cleaning unit cleans the sheet.

2. The cleaning apparatus according to claim 1, wherein the drive mechanism rotates the cleaning member.

3. The cleaning apparatus according to claim 1, wherein the holding unit includes a clamp that is movable selectively into a securing position for securing the

workpiece and a releasing position for releasing the workpiece, and a lock mechanism for locking the clamp placed in the securing position.

4. The cleaning apparatus according to claim 1, wherein the cleaning unit further includes a nozzle for supplying a fluid to the cleaning member.